

PTO-1449		Application No.		Applicant(s)		Page 1 of 1	
Information Disclosure Citation In an Application		10/849,192		Mohammed N. Islam et al.			
		Docket Number		Group Art Unit		Filing Date	
		074038.0127		2872		August 27, 2003	
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		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	A						
	B						
	C						
	D						
	E						
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	H						
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FOREIGN PATENT DOCUMENTS							
		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
	N						YES NO
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88	Q	Y. Chen, et al., "Modeling and Control of Nanomirrors for EUV Maskless Lithography," Technical Proc. Int. Conf. Modeling and Simulations of Microsystems, San Diego, CA, 3 pages					March 2000
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EXAMINER				DATE CONSIDERED			
<i>Patricia J. J. J.</i>				4 AUGUST 2004			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.							

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Information Disclosure Citation in an Application		10/649,192		Mohamm d N. Islam et al.	
		Docket Number		Group Art Unit	
		074036.0127		2872	
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NON-PATENT DOCUMENTS

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EXAMINER *John Zula* DATE CONSIDERED **4 AUGUST 2004**

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